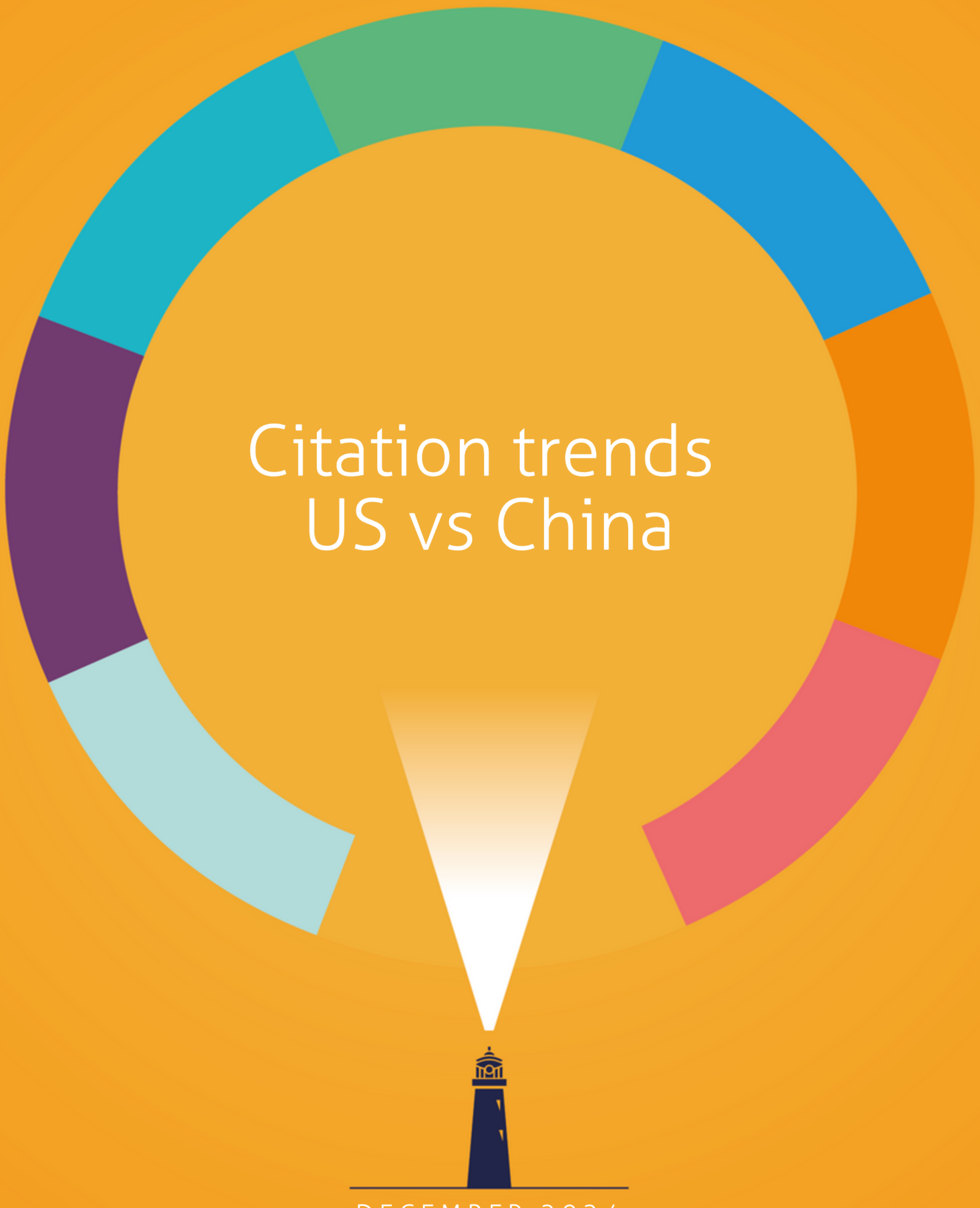
TREND REPORT



Citation trends US vs China

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Introduction

In the process of patent examination, the most critical thing is to comment on the novelty and creativity of the examined patent by comparing the previous patent technologies. Therefore, analyzing the patent cited by the patent examiner is interesting and meaningful work. In this report, the cited patents of patent examiners in the United States and China are counted and compared over the past five years, to understand the similarities and differences of citation trends the United States and China (Data as of December 23, 2024).

Part 1:
General Information

Both the United States and China have a large number of invention patent applications, and the number of invention patent applications in China has been significantly higher than that in the United States in recent years (as shown in Figure 1).

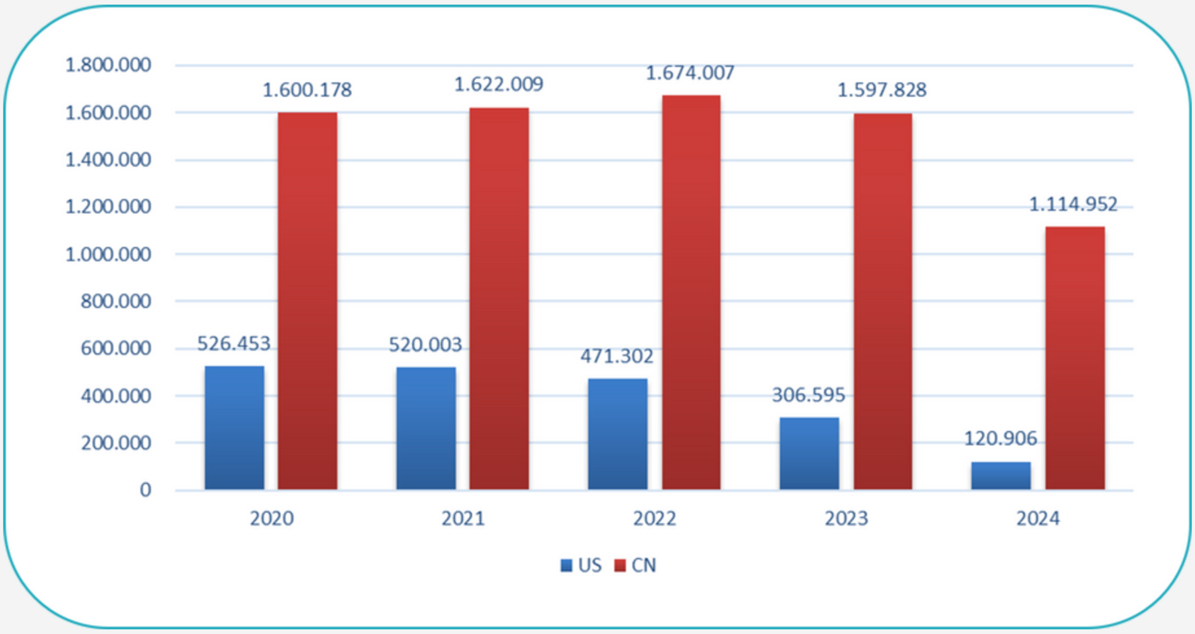

Figure 1 Application trend of invention patents US vs China

Meanwhile, the proportion of patents granted in the United States is higher than that in China (as shown in Figure 2). Obviously, the United States and Chinese patent examiners need to examine a large volume of patents every year.

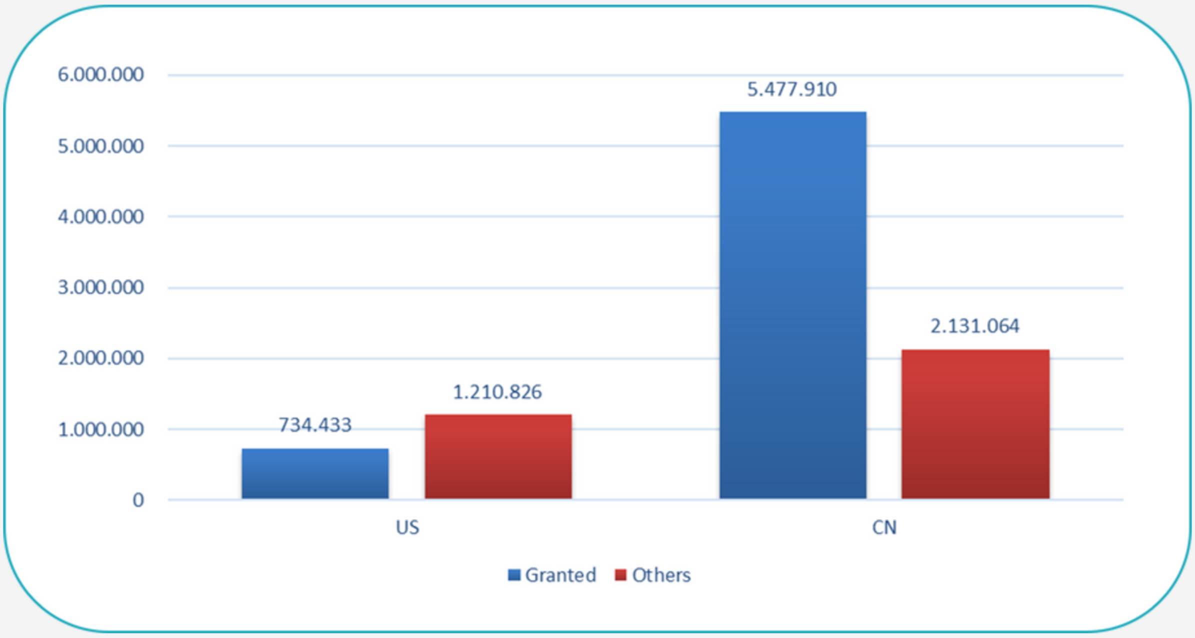

Figure 2 Patent granted status US vs China

Part 2:
Citation Category

The categories of citations cited by the examiner mainly include Class X documents (for commenting on the novelty of patents), Class Y documents (for commenting on the creativity of patents) and Class A documents (as the background technology of patents).

Both China and the United States have cited Class A documents the most in patent examination, while citing Class X documents the least (as shown in Figure 3).

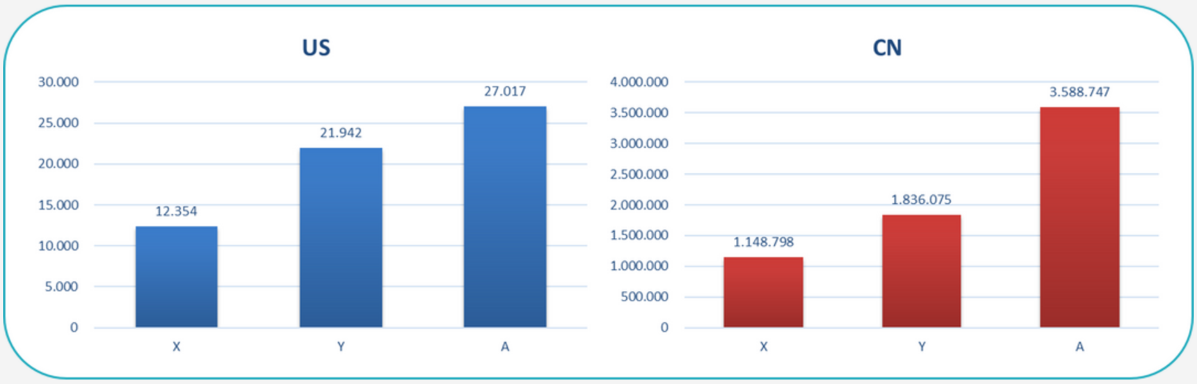

Figure 3 Citation categories US vs China

When the citation in the process of patent examination is Class X or Y documents, it means that the patent needs to be modified to be granted or cannot be granted. Through further statistical analysis, it is found that the proportion of patent documents cited by the United States patent examiners as Class X or Y documents is 75.46%, and that of China is 67.43% (as shown in Figure 4).

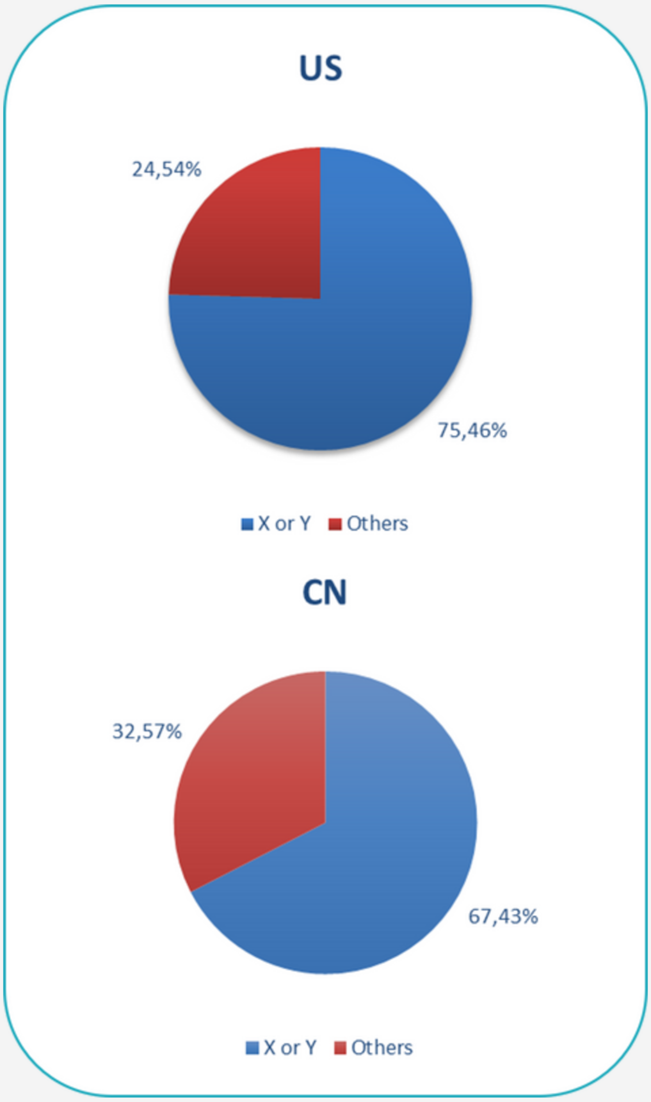

Figure 4 Proportion of patent citations involving X/Y documents US vs China

Part 3:
Citation Origin

Through the analysis of citation origin, we can understand the current technology concerns of examiners in different countries. Due to the large number of citations in the process of patent examination in the United States and China, this report selects 50,000 patents recently examined by the examiners of the two countries to analyze the origin of citations. The patents cited by the United States and China are mainly domestic patents, with a relatively low proportion of foreign patents. Relatively speaking, China cites more foreign patents (as shown in Figure 5).

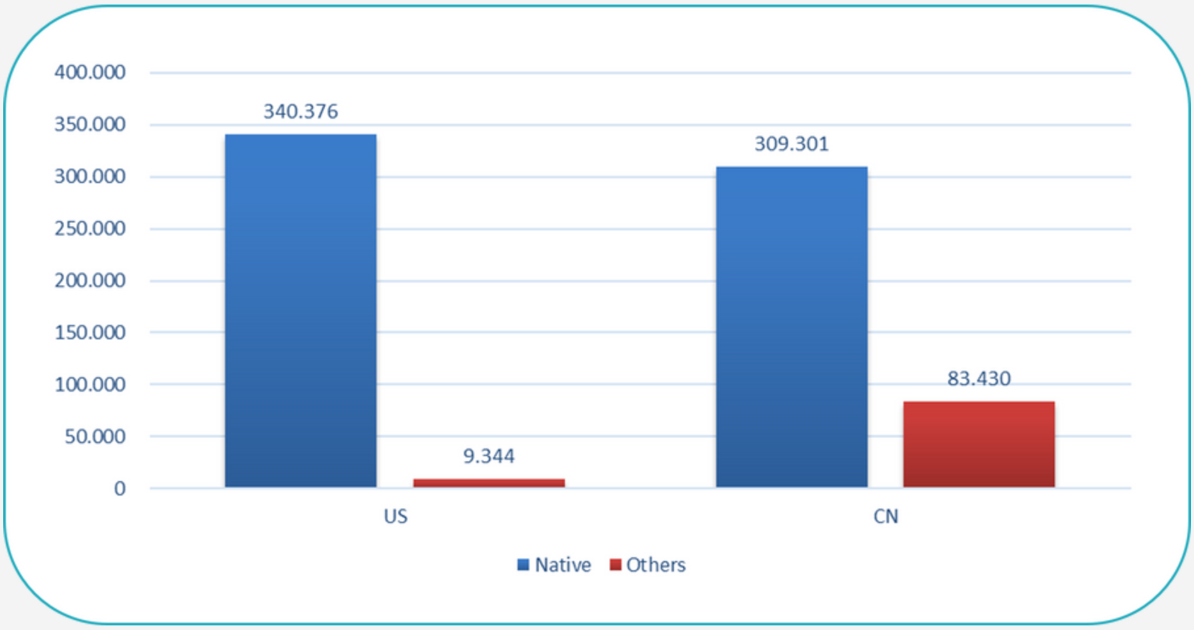

Figure 5 Origin of cited patents US vs China

Further analysis shows that among the foreign patents cited by the United States, patents from WIPO and Japan account for a relatively high proportion, while among the foreign patents cited by China, patents from the United States account for a relatively high proportion (as shown in Figure 6).

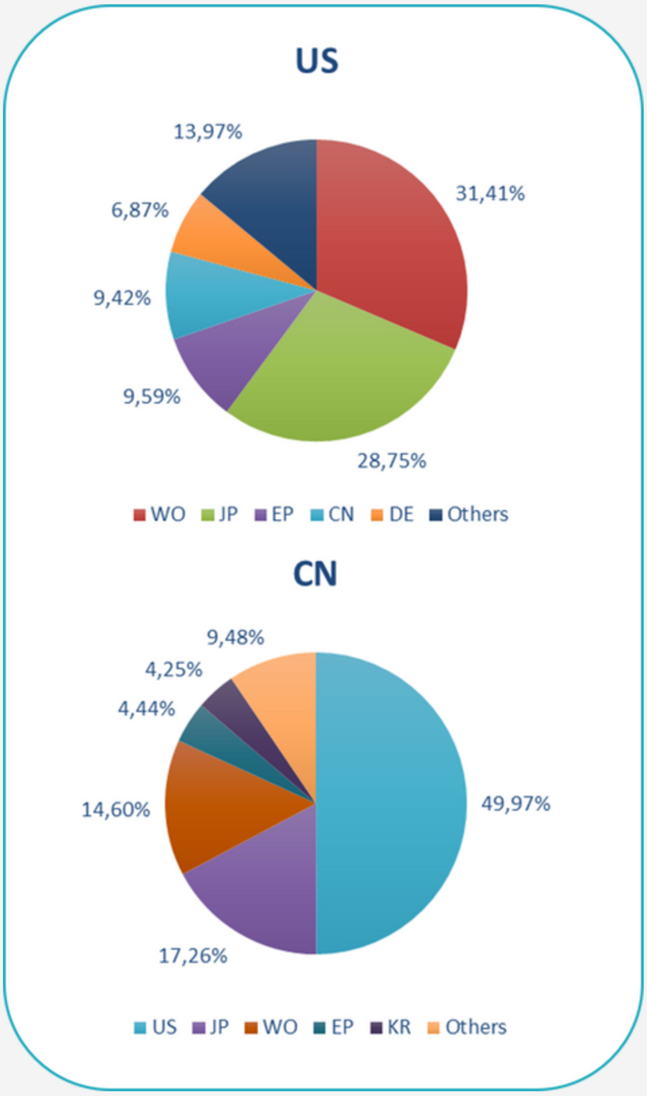

Figure 6 Foreign patents cited by US and China

Conclusion

In patent examination, both China and the United States cite many patents, mainly from their own countries.

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